

25. (Canceled)

26. (Previously presented) The metallization insulating structure according to claim 20 wherein the fluorine containing insulating layer comprises a material selected from the group consisting of fluorinated silicon oxide, fluorinated amorphous carbon, fluorinated diamondlike carbon and fluorinated organic polymers.

27. (Previously presented) The metallization structure of claim 21 wherein the metal structure extends through the capping layer such that the height of the structure is greater than  $h_i + h_f$ .

28. (canceled)

29. (Previously presented) The structure of claim 21 wherein the metal structure is in contact with the underlying metal structures through the capping layer.

#### REMARKS

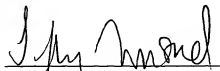
Claims 20 - 24, 26, 27 and 29 are pending in the instant application. Applicant's have previously presented documentation claiming priority to SN 08/744,846, now USPN

6,310,300. Generally, support for all elements of independent claim 20 can be found in the parent, priority document. Specifically, there is support in the specification at, at least, col. 4, line 58 - col. 5 line 1 and figures 2a - 2f generally and figure 2b specifically. None of the art cited in the Office Action dated 6/10/2003 is available as a reference as the priority date of each of those patents cited is after the priority date of the instant parent, priority document.

Consideration and allowance of claims 20 - 24, 26, 27 and 29 is respectfully requested.

Respectfully submitted,  
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